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(45) **Date of Patent:** Aug. 7, 2012

(56) **References Cited**

U.S. PATENT DOCUMENTS

6,864,946	B2	3/2005	Kim	
6,897,920	B2	5/2005	Lee et al.	
6,975,379	B2	12/2005	Kim et al.	
7,286,199	B2	10/2007	Moriya	
2003/0071956	A1	4/2003	Sasaki et al.	
2003/0117541	A1 *	6/2003	Kim et al.	349/43
2005/0110922	A1 *	5/2005	Lee et al.	349/106
2005/0157234	A1	7/2005	Park	

FOREIGN PATENT DOCUMENTS

JP	4-068314	3/1992
JP	9-043616	2/1997
JP	10-186374	7/1998
JP	2005-165239	6/2005
JP	2005-321495	11/2005

* cited by examiner

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(57) **ABSTRACT**

A liquid crystal display (LCD) device and a method of manufacturing the same that can improve the picture quality are provided. A liquid crystal display device includes: a first substrate; a black matrix formed in a matrix configuration on the first substrate; a compensation layer disposed above the black matrix and including a plurality of compensation patterns separated a predetermined region from each other where the compensation layer has been removed; and a column spacer disposed in a region including at least the predetermined region.

10 Claims, 11 Drawing Sheets

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(52) **U.S. Cl.** **349/155; 349/117; 349/106; 349/110**

(58) **Field of Classification Search** 349/155.

Field of Classification Search 349/106, 117, 110, 153, 155

See application file for complete search history.

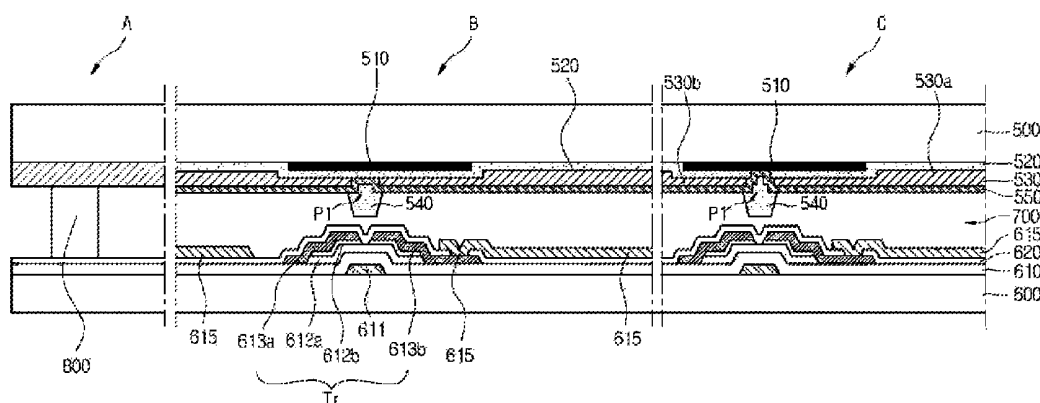


FIG. 1

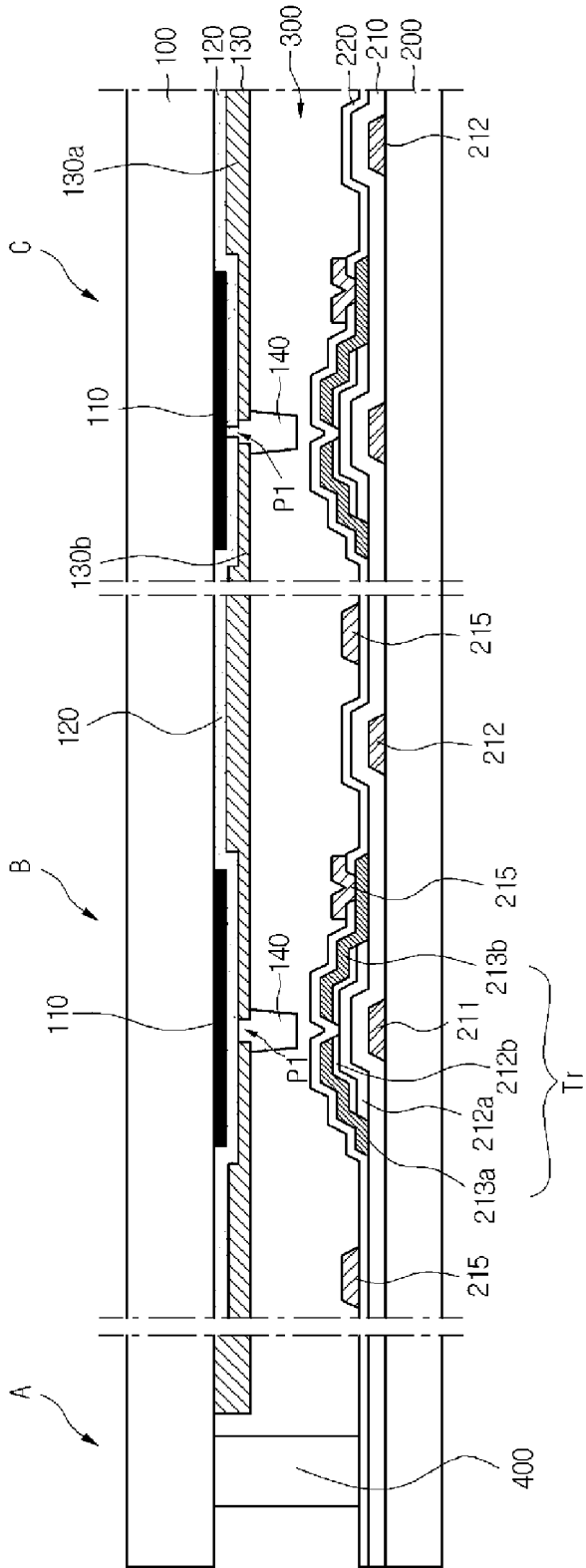


FIG. 2A

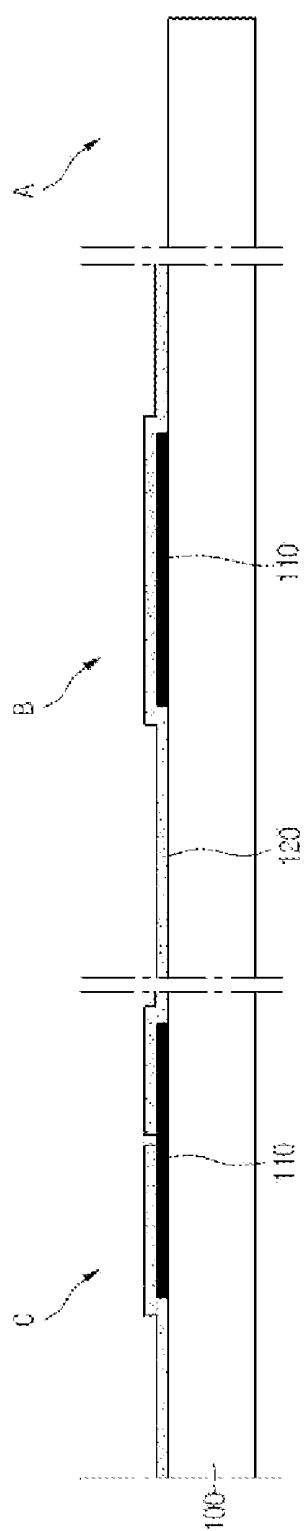


FIG. 2B

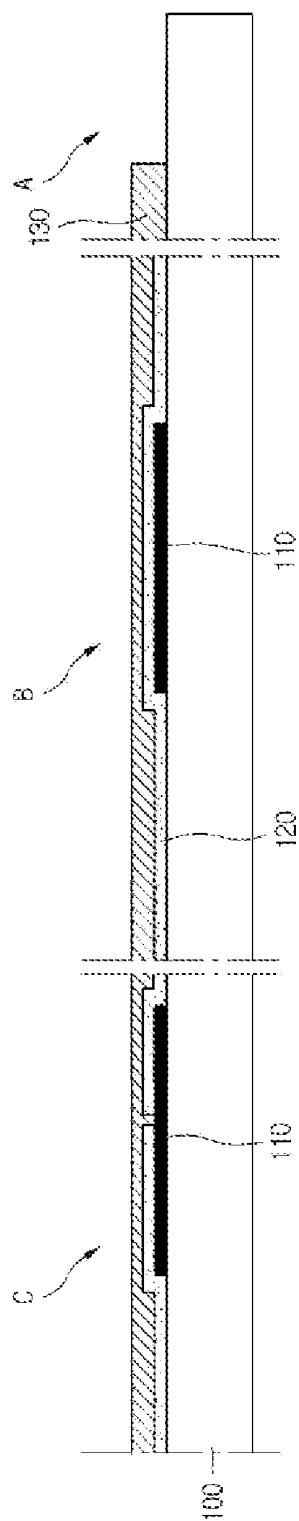


FIG. 2C

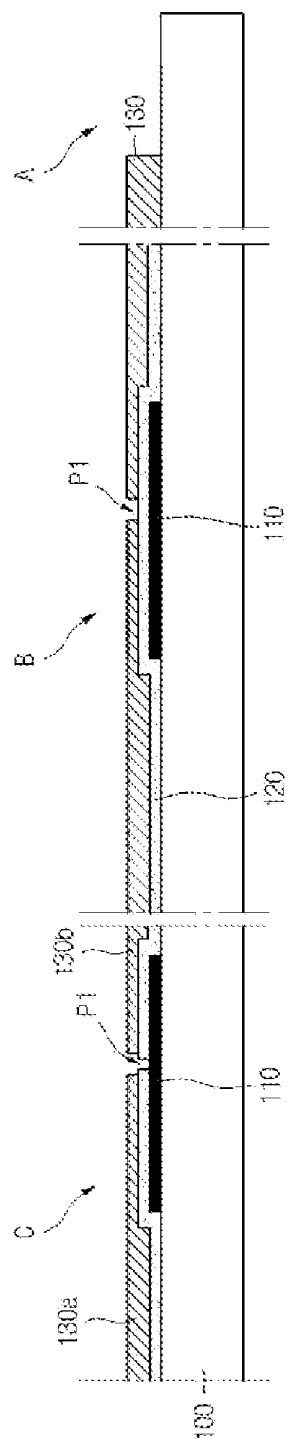


FIG. 2D

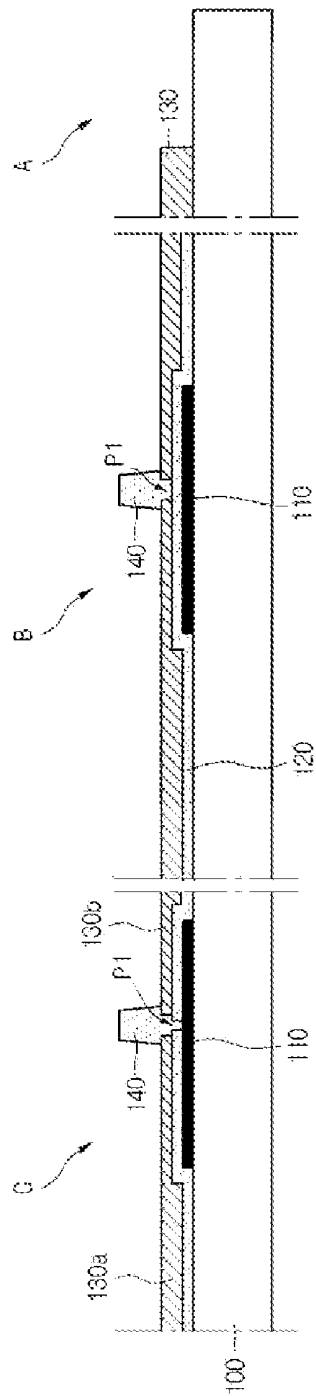


FIG. 2E

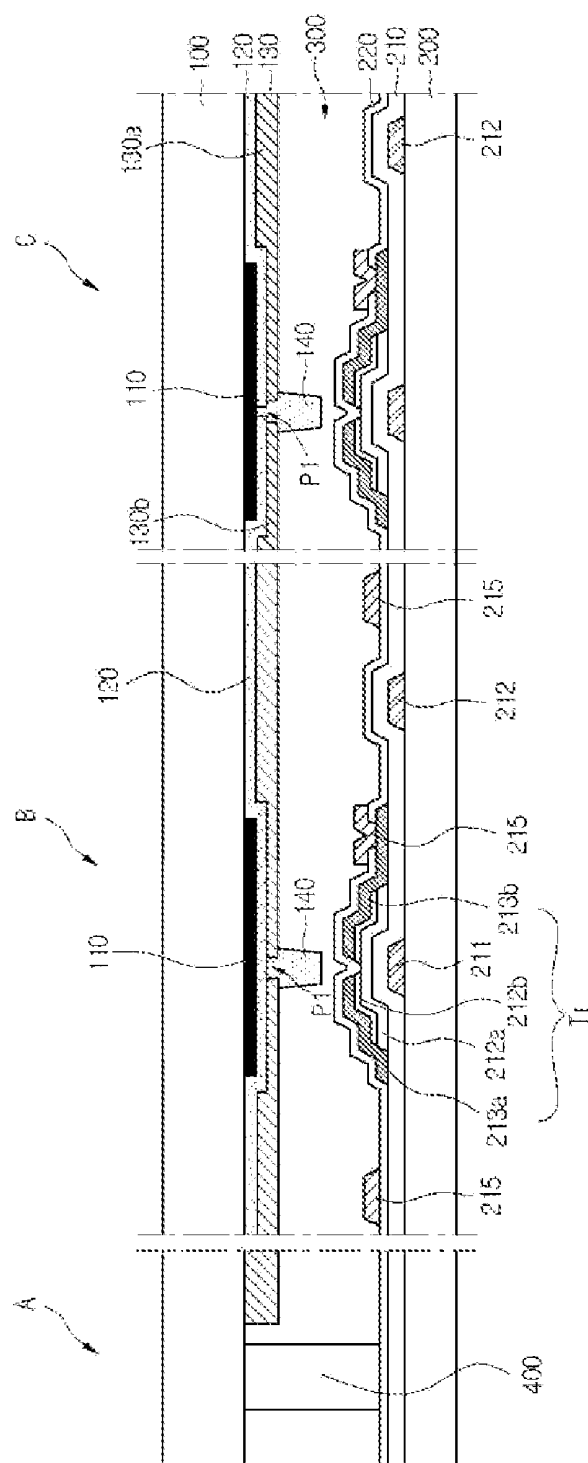


FIG. 3

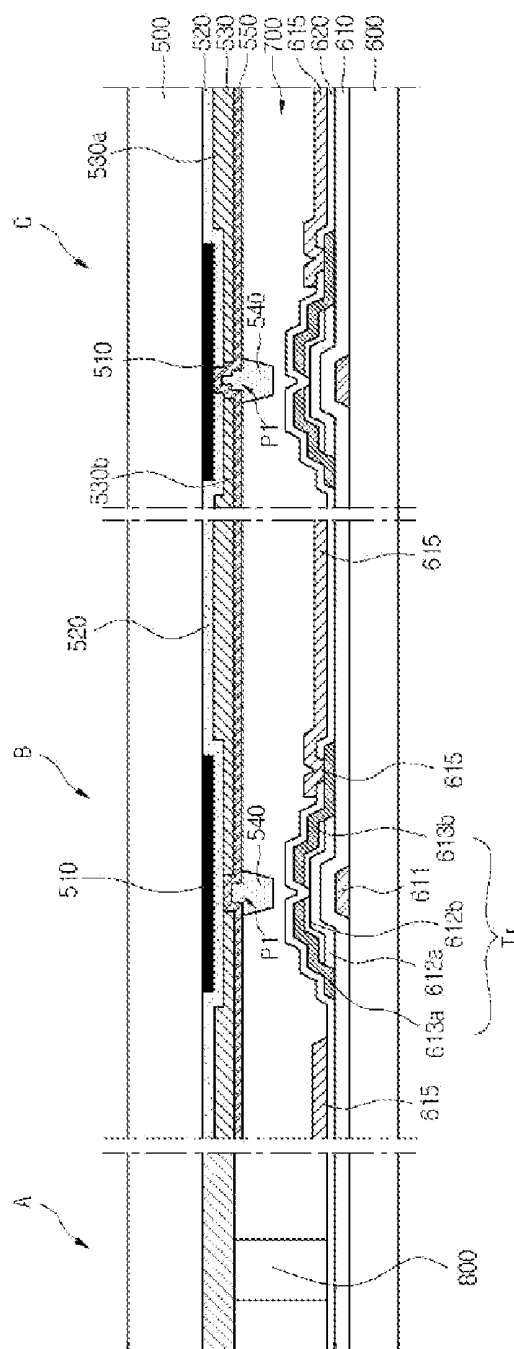


FIG. 4A

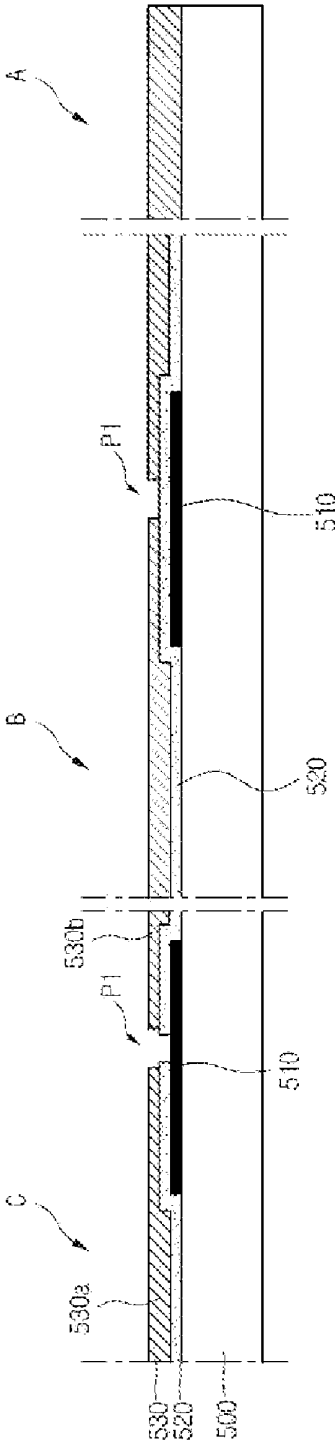


FIG. 4B

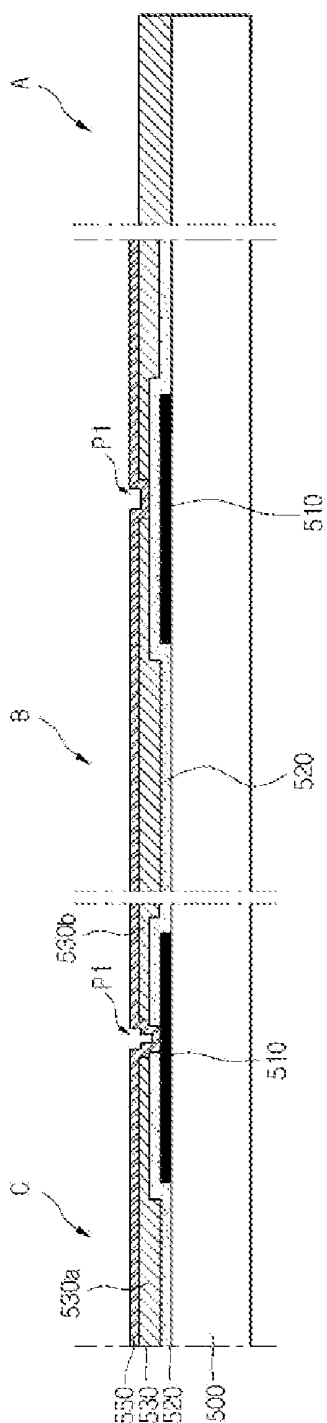
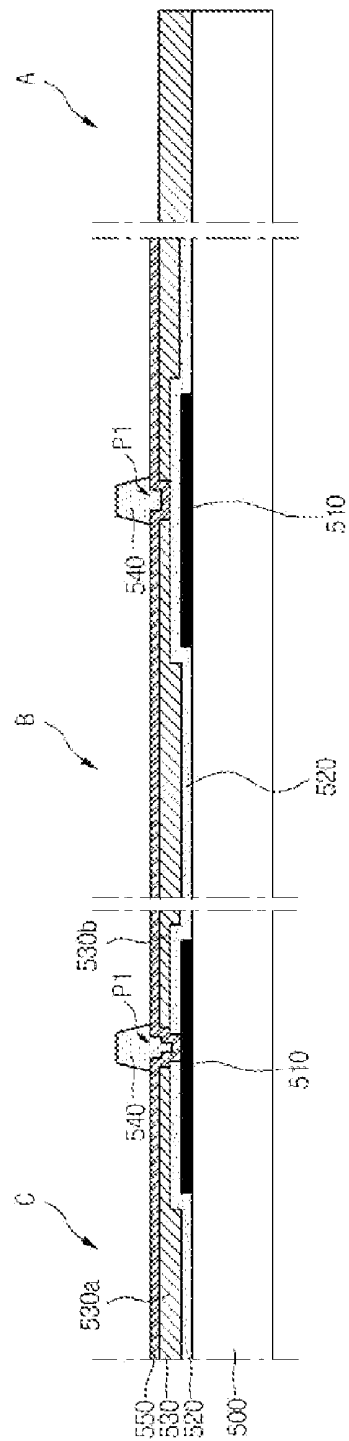


FIG. 4C



LIQUID CRYSTAL DISPLAY DEVICE AND METHOD OF MANUFACTURING THE SAME

This application is a Divisional of application Ser. No. 11/641,001 filed Dec. 19, 2006 now U.S. Pat. No. 8,027,010, now allowed, which claims priority to Korean Patent Application No. 10-2006-0014442, filed Feb. 15, 2006, all of which are incorporated by reference in their entirety for all purposes as if fully set forth herein.

BACKGROUND OF THE INVENTION

1. Field of the Invention

The present invention relates to a liquid crystal display device, and more particularly, to a liquid crystal display device including a compensation layer formed on an inner surface of a substrate and a method of manufacturing the same.

2. Discussion of the Related Art

With the development of modern information and communication technologies, liquid crystal display (LCD) devices having high brightness, large-sized screens, low power consumption and low price are in demand.

The LCD device includes first and second substrates having first and second electrodes, respectively that are attached such that the first electrode faces the second electrode, and a liquid crystal layer interposed between the first and second substrates. The LCD device displays an image using light transmittance that is changed when liquid crystal molecules are moved by an electric field generated by applying a voltage between the first and second electrodes.

Because the liquid crystal is optically an anisotropic material having an ordinary refractive index and an extra-ordinary refractive index, it has characteristics where the light path and birefringence vary depending on an incident angle of light. When the light emitted from a backlight is linearly polarized through a lower polarizing film of a liquid crystal panel and then passes through the liquid crystal having the optical anisotropy in a direction (case I) perpendicular to the liquid crystal cell and at a predetermined angle (case II) with respect to the liquid crystal cell, retardation values in cases I and II are different, and thus a phase difference is generated. As a result, the characteristics of light passing through the liquid crystal in the cases I and II are different according to the viewing angle.

Therefore, the related art LCD device has a low visibility due to a variation of contrast ratio and gray scale inversion, that are characteristics determining how clearly an image is seen.

The above problem can be overcome by compensating the optical phase difference generated in the liquid crystal cell, thereby enhancing the viewing angle. Therefore, a compensation film that can compensate for the optical phase difference is attached on a substrate to enhance the viewing angle.

However, when the compensation film is attached on the substrate, foreign particles may adhere to the compensation film. Also, the attached compensation film limits reducing the thickness of the liquid crystal panel. To solve these problems, there has been research into a compensation layer for compensating the optical phase difference formed on an inner surface of the substrate to thereby prevent foreign particles from adhering and decreasing the thickness of the liquid crystal panel.

The compensation layer is formed on the entire inner surface of the substrate, and a column spacer for maintaining a cell gap between two substrates is formed on the compensation layer. Because the compensation layer is formed of a

weak material with a weak restoring force, any pressure applied to the LCD device causes the column spacer to compress the compensation layer. Thereafter, when the pressure is released, the compensation layer does not return to its original state and thickness due to its weak restoring force. Therefore, the cell gap between two substrates decreases, which may result in a blemish.

Also, because the compensation layer is formed on the entire inner surface of the substrate, a seal pattern disposed along edges of the LCD device is formed on the compensation layer. However, because an adhesive force between the compensation layer and the seal pattern is very weak, a defect, such as a seal pattern burst may occur.

SUMMARY OF THE INVENTION

Accordingly, the present invention is directed to a liquid crystal display device and method for manufacturing the same that substantially obviates one or more of the problems due to limitations and disadvantages of the related art.

An advantage of the present invention is to provide a liquid crystal display device and a method of manufacturing the same that may enhance the viewing angle and decrease contamination due to foreign particles by forming a compensation layer on an inner surface of a substrate.

Another advantage of the present invention is to provide a liquid crystal display device and a method of manufacturing the same that may reduce the thickness of the liquid crystal display device by forming a compensation layer on an inner surface of a substrate.

Another advantage of the present invention is to provide a liquid crystal display device and a method of manufacturing the same that may maintain the cell gap between two substrates by removing a portion of a compensation layer corresponding to a column spacer.

Another advantage of the present invention is to provide a liquid crystal display device and a method of manufacturing the same that may prevent a seal pattern burst by removing a portion of compensation layer corresponding to a seal pattern region.

Additional features and advantages of the invention will be set forth in part in the description which follows, and in part will be apparent from the description, or may be learned by practice of the invention. The objectives and other advantages of the invention will be realized and attained by the structure particularly pointed out in the written description and claims hereof as well as the appended drawings.

To achieve these and other advantages and in accordance with the purpose of the present invention, as embodied and broadly described herein, a liquid crystal display device includes: a first substrate; a black matrix formed in a matrix configuration on the first substrate; a compensation layer disposed above the black matrix and including a plurality of compensation patterns separated a predetermined region from each other where the compensation layer has been removed; and a column spacer disposed in a region including at least the predetermined region.

In another aspect of the present invention, a liquid crystal display device includes: a first substrate; a black matrix formed in a matrix configuration on the first substrate; a compensation layer disposed above the black matrix and including a plurality of compensation patterns separated by a predetermined region from each other where the compensation layer has been removed; a column spacer disposed in a region including at least the predetermined region; a second substrate disposed facing the first substrate; and a liquid crystal layer interposed between the first substrate and the second

substrate, wherein the second substrate includes a pixel electrode and a common electrode alternately arranged thereon.

In still another aspect of the present invention, a liquid crystal display device includes: a first substrate; a black matrix formed in a matrix configuration on the first substrate; a compensation layer disposed above the black matrix and including a plurality of compensation patterns separated by a predetermined region from each other where the compensation layer has been removed; a common electrode formed on the first substrate including the compensation patterns; a column spacer formed on the common electrode corresponding to the black matrix; a second substrate disposed facing the first substrate; and a liquid crystal layer interposed between the first substrate and the second substrate, wherein the second substrate includes a pixel electrode formed thereon.

In yet another aspect of the present invention, a method of manufacturing a liquid crystal display device, includes: forming a black matrix in a matrix configuration on a first substrate; forming a compensation pattern including a plurality of compensation patterns separated by a predetermined region from one another on the black matrix where the compensation layer has been removed; and forming a column spacer on the first substrate including the predetermined region.

It is to be understood that both the foregoing general description and the following detailed description of the present invention are exemplary and explanatory and are intended to provide further explanation of the invention as claimed.

BRIEF DESCRIPTION OF THE DRAWINGS

The accompanying drawings, which are included to provide a further understanding of the invention and are incorporated in and constitute a part of this specification, illustrate embodiment(s) of the invention and together with the description serve to explain the principle of the invention.

In the drawings:

FIG. 1 is a sectional view of an IPS mode LCD device according to a first embodiment of the present invention;

FIGS. 2A through 2E are schematic sectional views illustrating a process of manufacturing an IPS mode LCD device according to a first embodiment of the present invention;

FIG. 3 is a sectional view of a TN mode LCD device according to a second embodiment of the present invention; and

FIGS. 4A through 4D are schematic sectional views illustrating a process of manufacturing a TN mode LCD device according to a second embodiment of the present invention.

DETAILED DESCRIPTION OF THE ILLUSTRATED EMBODIMENTS

Reference will now be made in detail to an embodiment of the present invention, examples of which is illustrated in the accompanying drawings.

FIG. 1 is a sectional view of an IPS mode LCD device according to a first embodiment of the present invention.

Referring to FIG. 1, first and second substrates **100** and **200** are spaced apart by a predetermined distance from each other, and a liquid crystal layer **300** is interposed between the first and second substrates **100** and **200**. A seal pattern **400** is formed in an edge region (i.e., seal pattern region, 'A') of the first and second substrates **100** and **200**. The first and second substrates **100** and **200** are attached to one another by the seal pattern **400**.

On an inner surface of the first substrate **100** are formed a black matrix **110** and a color filter layer **120**.

The black matrix **110** is arranged in a matrix configuration corresponding to a non-transmission region of the second substrate **200**. The non-transmission region includes gate lines and a data lines defining pixel regions of the second substrate **200**, thin film transistors formed at a crossing of the gate line and the data line, and the edge region 'A'.

The color filter layer **120** is formed corresponding to a transmission region of the second substrate **200**. The transmission region includes a plurality of pixel regions defined by the gate lines and the data lines. The color filter layer **120** has different colors corresponding to the respective pixel regions. The color filter layer **120** is formed corresponding to the pixel regions and is also formed partially overlapping the black matrix **110** on the black matrix **110**. Accordingly, the color filter layer **120** on the black matrix **110** can be divided into first color filter layer and second color filter layer separated by a predetermined distance from each other that is shown in region 'C' of FIG. 1.

As shown in region 'B' of FIG. 1, when the color filter layer **120** is arranged in a striped configuration, the color filter layer **120** on the black matrix **110** has the same color and thus the color filter layer is integrally formed without being separated from each other.

In summary, when the color filter layer **120** is arranged in a striped configuration, R, G and B color filters may be arranged in a vertical direction. At this time, adjacent color filters are formed separated from one another on the black matrix in a horizontal direction. Meanwhile, because the same color filters are formed on the black matrix **110** in the vertical direction, they are not separated from one another but are integrally formed with one another.

Hereinafter, the present invention will be described with an example where the color filter layer is formed in a striped configuration in the vertical direction.

A compensation layer **130** is formed on the black matrix **110** and the color filter layer **120**. The compensation layer **130** includes a plurality of compensation patterns **130a** and **130b** spaced apart from each other. The compensation patterns **130a** and **130b** function to compensate for an optical phase difference and at the same time serves as an overcoating layer to compensate for a height difference between the black matrix **110** and the color filter layer **120**. The compensation patterns **130a** and **130b** may be formed of reactive mesogen that may compensate for light leakage.

The compensation patterns **130a** and **130b** are separated from each other on the black matrix **110** by a predetermined region 'P1'. In other words, the compensation patterns **130a** and **130b** are not integrally formed across all regions on the black matrix **110** but are formed by removing the predetermined region 'P1'. Because the compensation pattern is removed in the predetermined region 'P1', the compensation patterns **130a** and **130b** do not exist in the predetermined region 'P1'. As a result, the compensation patterns **130a** and **130b** on the black matrix are separated from one another by the predetermined region 'P1'. It is preferable that the predetermined region 'P1' corresponds to a column spacer **140** to be described later. The reason is as follows. If the region 'P1' has a size corresponding to a size of the column spacer **140**, the compensation patterns **130a** and **130b** are not compressed by the column spacer **140**, thereby preventing a blemish defect due to a recovery failure of the compensation patterns **130a** and **130b** that do not recover after being compressed.

The column spacer **140** for maintaining a cell gap between the first and second substrates **100** and **200** is formed on the

first substrate **100** in the predetermined region 'P1' between the compensation patterns **130a** and **130b**.

In this case, the column spacer **140** has different contact positions in the vertical direction (region 'B' of FIG. 1) and in the horizontal direction (region 'C' of FIG. 1).

For example, in the case of the horizontal direction (region 'C' of FIG. 1), the column spacer **140** can locally contact the black matrix **110**, the color filter layer **120** and the compensation patterns **130a** and **130b**. That is, in the case of the horizontal direction (region 'C' of FIG. 1), because the color filters of the color filter layer **120** are separated by a predetermined distance from one another and the compensation patterns **130a** and **130b** are separated by the predetermined region 'P1', the column spacer **140** passes through the predetermined region 'P1' between the compensation patterns **130a** and **130b** to locally contact both sidewalls of the color filter layer **120**, and also passes through the predetermined distance to contact the black matrix **110**. Also, because the column spacer **140** has a diameter at least larger than the predetermined region 'P1' between the compensation patterns **130a** and **130b**, the column spacer **140** contacts both upper edge surfaces of the compensation patterns **130a** and **130b** and is centered on the predetermined region 'P1' between the compensation patterns **130a** and **130b**.

In the case of the vertical direction (region 'B' of FIG. 1), the column spacer **140** contacts the color filter layer **120** and the compensation patterns **130a** and **130b**. That is, in the case of the vertical direction (region 'B' of FIG. 1), because the color filters of the color filter layer **120** are not separated from one another but are integrally formed with one another, the column spacer **140** passes through the predetermined region 'P1' between the compensation patterns **130a** and **130b** to locally contact the color filter layer **120**. Also, because the column spacer **140** has a diameter at least larger than the predetermined region 'P1' between the compensation patterns **130a** and **130b**, the column spacer **140** contacts both upper edge surfaces of the compensation patterns **130a** and **130b** and is centered on the predetermined region 'P1' between the compensation patterns **130a** and **130b**.

It is preferable that the area where the column spacer **140** contacts the compensation pattern **130a** and **130b** is as small as possible. By doing so, because the compensation patterns **130a** and **130b** on the black matrix **110** are separated by the predetermined region 'P1' from each other and the column spacer **140** mainly contacts the color filter layer **120** or the black matrix **110**, a blemish defect due to a recovery failure of the compensation patterns **130a** and **130b** that do not recover after being compressed can be prevented.

Meanwhile, the compensation patterns **130a** and **130b** are not formed in the edge region 'A' of the first and second substrates **100** and **200**. For this purpose, the compensation patterns **130a** and **130b** formed on the edge region 'A' can be removed.

The seal pattern **400** directly contacts the first substrate **100** at the edge region 'A' where the compensation patterns **130a** and **130b** are not formed. Accordingly, the seal pattern **400** has a strong bond to the first substrate **100**, thus preventing the seal pattern from bursting due to a contact failure of the seal pattern.

Meanwhile, gate lines (not shown) are arranged in the horizontal direction on the inner surface of the second substrate **200**, and data lines (not shown) are arranged in the vertical direction crossing the gate lines. As the gate lines cross the data lines, a pixel region is defined. A thin film transistor 'Tr' is disposed around an area where the gate lines and the data lines cross, and a common line (not shown) is arranged in parallel with the gate lines within the pixel region.

A plurality of common electrodes **212** branch from the common line. A pixel electrode **215** is connected to the thin film transistor 'Tr'. The pixel electrode **215** and the common electrode **212** are arranged in an alternating pattern.

The thin film transistor 'Tr' includes a gate electrode **211** branching from the gate line, a gate insulation layer **210** formed on the second substrate **200** including the gate electrode **211**, an active layer **212** disposed on the gate insulation layer **210** corresponding to the gate electrode **211**, and including a channel layer **212a** and an ohmic contact layer **212b** stacked thereon, and a source/drain electrode **213a/213b** disposed on both edges of the active layer **212**.

A passivation layer **220** is disposed on the second substrate **200** including the source/drain electrode **213a/213b**. The pixel electrode **215** is disposed on the passivation layer **220**, and the pixel electrode **215** and the common electrode **212** are arranged in turn.

When a predetermined voltage is applied between the common electrode **212** and the pixel electrode **215**, a fringe field is formed between the common electrode **212** and the pixel electrode **215**. The formed fringe field realigns the liquid crystal molecules to enhance the viewing angle.

However, when the IPS mode LCD device is in a dark state, light is leaked and thus a contrast ratio is lowered, which is problematic.

To solve this problem, the compensation patterns **130a** and **130b** are formed on the inner surface of the first substrate **100**. The compensation patterns **130a** and **130b** can compensate light leakage leaked in the dark state of the inclined angle. The second substrate **200** adjusts the alignment of the liquid crystal molecules to enhance the viewing angle, thus enabling manufacture of an IPS mode LCD device that can improve the picture quality.

Also, the compensation patterns **130a** and **130b** on the black matrix **110** are separated by the predetermined region 'P1', and the column spacer **140** is formed on the predetermined region 'P1', thereby preventing a blemish defect due to a recovery failure of the compensation patterns **130a** and **130b** that do not recover after being compressed.

Also, because the column spacer **140** is formed on the black matrix **110** without being influenced by the compensation patterns **130a** and **130b**, a constant cell gap between the first and second substrates **100** and **200** may be stably maintained.

Further, because the compensation patterns **130a** and **130b** are not formed in the edge region 'A' of the first and second substrates **100** and **200** and thus the seal pattern **400** has a strong bond to the first substrate **100**, thus preventing the seal pattern from bursting, due to a contact failure of the seal pattern.

FIGS. 2A and 2B are schematic sectional views illustrating a process of manufacturing an IPS mode LCD device according to a first embodiment of the present invention.

Referring to FIG. 2A, a black matrix **110** and a color filter layer **120** are formed on a first substrate **100**. The black matrix **110** is arranged corresponding to non-transmission regions of the display and thus it has a matrix configuration in which horizontal lines cross vertical lines. The color filter layer **120** is arranged in a striped configuration. If necessary, the color filters of the color filter layer **120** are arranged in the order of R, G and B or in the order of R, G, G and B. For example, the color filter layer is arranged between the vertical lines of the black matrix **110** in the horizontal direction, and some of the color filter layer **120** is formed partially overlapping vertical lines of the black matrix **110** on the black matrix **110**. Accordingly, the color filter layer **120** on the vertical line of the black matrix **110** is arranged divided into two parts. Because the

color filter layer **120** is arranged as one body in the vertical direction and passes over the horizontal lines of the black matrix **110**, the color filter layer **120** is not divided on the horizontal lines of the black matrix **110** but is integrally formed.

The black matrix **110** may be formed by coating an opaque material film on the first substrate **100**, exposing and developing the coated opaque material film, and hardening the developed opaque material film. The opaque material film may be formed of carbon black or titanium oxide. The color filter layer **120** may be formed by coating a photoresist film including a pigment for color display in a transmission region, exposing and developing the coated photoresist film, and hardening the developed photoresist film.

Referring to FIG. 2B, a compensation layer **130** is formed on the first substrate **100** including the black matrix **110** and the color filter layer **120**. The compensation layer **130** may be formed of a material including a reactive mesogen by an ink jet method, a roll printing method, a screen printing method, a bar coating method and a spin coating method.

Thereafter, a mask is aligned over the compensation layer **130** and an exposure process is performed to irradiate light onto a predetermined region on the black matrix **110** and the edge region 'A' of the first substrate **100**, i.e., a region except for the seal pattern region, thereby hardening corresponding portions of the compensation layer **130**.

Referring to FIG. 2C, the compensation layer **130** is developed using a developing solution including acetone, ethanol, or poly glycidyl methacrylate (PGMA), so that the compensation layer **130** in the predetermined region on the black matrix **110** and the compensation layer **130** of the seal pattern region 'A' are removed to form a plurality of compensation patterns **130a** and **130b**.

Referring to FIG. 2D, a photoresist film is coated on the first substrate **100** including the compensation patterns **130a** and **130b** and then patterned to form a column spacer **140**. The column spacer **140** is formed in the predetermined region 'P1' between the compensation patterns **130a** and **130b** on the black matrix **110**. Accordingly, the column spacer **140** passes through the predetermined region 'P1' between the compensation patterns **130a** and **130b** and is formed on the color filter layer **120**. Alternatively, the column spacer **140** passes through the predetermined region 'P1' between the compensation patterns **130a** and **130b** and the predetermined spacing of the color filter layer and is formed on the black matrix **110**.

Referring to FIG. 2E, a second substrate **200** facing the first substrate **100** is provided.

The second substrate **200** includes a gate line, a data line crossing the gate line, a thin film transistor 'Tr' at a crossing point of the gate line and the data line, a common line (not shown) disposed in parallel with the gate line within a pixel region, a plurality of common electrodes **212** branching from the common line, and a pixel electrode **215** alternatively disposed with the common electrodes.

After a seal pattern is formed in the edge region 'A' of the first substrate **100** and the second substrate **200**, the first substrate **100** and the second substrate **200** are attached, thus manufacturing an IPS mode LCD device.

Because the compensation patterns **130a** and **130b** are not formed in the edge region 'A' where the seal pattern is formed, the seal pattern can be attached to the first substrate **100** with a stronger adhesive force, thereby preventing a defect such as the seal pattern bursting.

FIG. 3 is a sectional view of a TN mode LCD device according to a second embodiment of the present invention.

Referring to FIG. 3, first and second substrates **500** and **600** are spaced apart by a predetermined distance from each other,

and a liquid crystal layer **700** is interposed between the first and second substrates **500** and **600**. A seal pattern **800** is formed in an edge region (i.e., seal pattern region, 'A') of the first and second substrates **500** and **600**. The first and second substrates **500** and **600** are attached to one another by the seal pattern **800**.

On an inner surface of the first substrate **500** are formed a black matrix **510** and a color filter layer **520**.

The black matrix **510** is arranged in a matrix configuration corresponding to a non-transmission region of the second substrate **600**. The non-transmission region includes gate lines and data lines defining pixel regions of the second substrate **600**, thin film transistors formed at a crossing of the gate line and the data line, and the edge region 'A'.

The color filter layer **520** is formed corresponding to a transmission region of the second substrate **600**. The transmission region includes a plurality of pixel regions defined by the gate lines and the data lines. The color filter layer **520** has different colors corresponding to the respective pixel regions. The color filter layer **520** is formed corresponding to the pixel regions and is also formed partially overlapping the black matrix **510** on the black matrix **510**. Accordingly, the color filter layer **520** on the black matrix **510** can be divided into first color filter layer and second color filter layer separated by a predetermined distance from each other that is shown in region 'C' of FIG. 3.

As shown in region 'B' of FIG. 3, when the color filter layer **520** is arranged in a striped configuration, the color filter layer **520** on the black matrix **510** has the same color and thus the color filter layer is integrally formed without being separated from each other.

In summary, when the color filter layer **520** is arranged in a striped configuration, R, G and B color filters may be arranged in a vertical direction. At this time, adjacent color filters are formed separated from one another on the black matrix in a horizontal direction. Meanwhile, because the same color filters are formed on the black matrix **510** in the vertical direction, they are not spaced from one another but are integrally formed with one another.

Hereinafter, the present invention will be described with an example where the color filter layer is formed in a striped configuration in the vertical direction.

A compensation layer **530** is formed on the black matrix **510** and the color filter layer **520**. The compensation layer **530** includes a plurality of compensation patterns **530a** and **530b**. The compensation patterns **530a** and **530b** function to compensate for an optical phase difference and at the same time serves as an overcoating layer to compensate for a height difference between the black matrix **510** and the color filter layer **520**. The compensation patterns **530a** and **530b** may be formed of reactive mesogen that may compensate light leakage.

The compensation patterns **530a** and **530b** are separated from each other on the black matrix **510** by a predetermined region 'P1'. In other words, the compensation patterns **530a** and **530b** are not integrally formed across all regions on the black matrix **510** but are formed by removing the predetermined region 'P1'. Because the compensation pattern is removed in the predetermined region 'P1', the compensation patterns **530a** and **530b** do not exist in the predetermined region 'P1'. As a result, the compensation patterns **530a** and **530b** on the black matrix are separated from one another by the predetermined region 'P1'.

A common electrode **550** is formed on the first substrate **500** including the compensation patterns **530a** and **530b**. The common electrode **550** may be formed of transparent indium tin oxide (ITO) or indium zinc oxide (IZO). Accordingly, the

common electrode **550** on the black matrix **510** passes through the predetermined region 'P1' between the compensation patterns **530a** and **530b** and contacts the color filter layer (see region 'B' of FIG. 3), or the common electrode **550** on the black matrix **510** passes through the predetermined region 'P1' of the compensation patterns **530a** and **530b** and the predetermined spacing of the color filter layer **520** and contacts a top surface of the black matrix **510** (see region 'C' of FIG. 3).

Accordingly, the common electrode **550** on the black matrix **510** has a groove shape recessed toward the black matrix **510**.

A column spacer **540** for maintaining a cell gap between the first and second substrates **500** and **600** is formed on the common electrode **550** corresponding to the predetermined region 'P1' between the compensation patterns **530a** and **530b**. Accordingly, the column spacer **540** is formed on the recessed groove of the common electrode **550** on the black matrix **510**. Because the compensation patterns **530a** and **530b** are not formed at a lower portion of the recessed groove, a blemish defect due to a recovery failure where the compensation patterns **530a** and **530b** do not recover after being compressed can be prevented. Eventually, because the compensation patterns **530a** and **530b** are not influenced at all by the column spacer **540**, the constant cell gap between the first and second substrates **500** and **600** may be stably maintained.

Meanwhile, the compensation patterns **530a** and **530b** are not formed in the edge region 'A' of the first and second substrates **500** and **600**, the common electrode **550** is formed on the first substrate **500** and the seal pattern **800** is formed on the common electrode **550**. Therefore, compared with the related art where the seal pattern is adhered to the compensation patterns with a weak adhesive force, the seal pattern **800** in the present invention adheres to the common electrode **550** with a stronger adhesive force, so that a defect such as a seal pattern burst can be prevented.

Meanwhile, the second substrate **600** includes a gate line (not shown) arranged in a first direction on an inner surface of the second substrate **600**, a data line (not shown) arranged in a second direction substantially perpendicular to the gate line, a thin film transistor 'Tr' at a crossing of the gate line and the data line, and a pixel electrode **615** connected to a drain electrode **613b** of the thin film transistor 'Tr'.

A plurality of insulation layers, e.g., a gate insulation layer **610** and passivation layer **620**, are formed on the second substrate **600** to prevent the lines from being short-circuited.

Thus, the compensation patterns **530a** and **530b** that compensate for the optical phase difference are formed on the inner surface of the first substrate **500**, so that a TN mode LCD device having an improved viewing angle can be manufactured.

Also, because the compensation patterns **530a** and **530b** are formed with an exposed column spacer region where an external force is concentrated, it is possible to maintain the constant cell gap between the first and second substrates **500** and **600**.

While the above embodiment shows and describes an example of a TN mode LCD device, it can be applied to other LCD devices, such as a VA mode LCD device, an OCB mode LCD device, an STN mode LCD device and the like.

FIGS. 4A through 4D are schematic sectional views illustrating a process of manufacturing a TN mode LCD device according to a second embodiment of the present invention.

Referring to FIG. 4A, a black matrix **510** and a color filter layer **520** are formed on a first substrate **500**. The black matrix **510** is arranged corresponding to non-transmission regions and thus it has a matrix configuration in which horizontal lines cross vertical lines. The color filter layer **520** is arranged in a striped configuration. If necessary, the color filters of the color filter layer **520** are arranged in the order of R, G and B

or in the order of R, G, G and B. For example, the color filter layer is arranged between the vertical lines of the black matrix **510** in the horizontal direction, and some of the color filter layer **520** is formed partially overlapping vertical lines of the black matrix **510** on the black matrix **510**. Accordingly, the color filter layer **520** on the vertical line of the black matrix **510** is arranged divided into two parts. Because the color filter layer **520** is arranged as one body in the vertical direction and passes over the horizontal lines of the black matrix **510**, the color filter layer **520** is not divided on the horizontal lines of the black matrix **510** but is integrally formed.

The black matrix **510** may be formed by coating an opaque material film on the first substrate **500**, exposing and developing the coated opaque material film, and hardening the developed opaque material film. The opaque material film may be formed of carbon black or titanium oxide. The color filter layer **520** may be formed by coating a photoresist film including a pigment for color display in a transmission region, exposing and developing the coated photoresist film, and hardening the developed photoresist film.

Thereafter, a plurality of compensation patterns **530a** and **530b** are formed by removing a predetermined region 'P1' of a compensation layer **530** formed over the black matrix **510**. The compensation layer **530** may be formed of a material including a reactive mesogen by an ink jet method, a roll printing method, a screen printing method, a bar coating method and a spin coating method.

Thereafter, a mask is aligned over the compensation layer and an exposure process is performed to irradiate light onto a predetermined region on the black matrix **510** and the edge region 'A' of the first substrate **500**, i.e., a region except for the seal pattern region, thereby hardening the regions.

Thereafter, the compensation layer is developed using a developing solution including acetone, ethanol, or poly glycidyl methacrylate (PGMA), so that the compensation layer **530** in the predetermined region on the black matrix **510** and the compensation layer **530** of the seal pattern region 'A' are removed to form compensation patterns **530a** and **530b**.

Referring to FIG. 4B, a common electrode **550** is formed on the first substrate **500** including the compensation patterns **530a** and **530b**. The common electrode **550** may be formed of transparent indium tin oxide (ITO) or indium zinc oxide (IZO) by a sputtering method. Accordingly, the common electrode **550** on the black matrix **510** passes through the predetermined region 'P1' between the compensation patterns **530a** and **530b** and contacts the color filter layer (see region 'B' of FIG. 3), or the common electrode **550** on the black matrix **510** passes through the predetermined region 'P1' between the compensation patterns **530a** and **530b** and the predetermined spacing of the color filter layer **520** and contacts a top surface of the black matrix **510** (see region 'C' of FIG. 3). The common electrode **550** on the black matrix **510** may have a groove shape recessed toward the black matrix **510** because the compensation patterns **530a** and **530b** do not exist at the predetermined region 'P1'.

Referring to FIG. 4C, a photoresist film is coated on the common electrode **550** and then patterned to form a column spacer **540**. The column spacer **540** is formed extending to the recessed groove region of the common electrode **550** on the black matrix **510**. Because the compensation patterns **530a** and **530b** are not formed in the groove region, a blemish defect due to a recovery failure where the compensation patterns **530a** and **530b** do not recover after being compressed can be prevented.

Referring to FIG. 4D, a second substrate **600** facing the first substrate **500** is provided.

The second substrate **600** includes a gate line, a data line crossing the gate line, a thin film transistor 'Tr' at a crossing

of the gate line and the data line, and a pixel electrode **615** electrically connected with a drain electrode of the thin film transistor 'Tr'.

After a seal pattern is formed in the edge region 'A' of the first substrate **500** and the second substrate **600**, the first substrate **500** and the second substrate **600** are attached, thus manufacturing a TN mode LCD device.

The compensation patterns **530a** and **530b** are not formed in the edge region 'A' of the first and second substrates **500** and **600**, the common electrode **550** is formed directly on the first substrate **500**, and the seal pattern is formed directly on the common electrode **550**. Therefore, compared with the related art where the seal pattern is adhered to the compensation pattern with a weak adhesive force, the seal pattern **800** in the present invention adheres to the common electrode **550** with a stronger adhesive force, and a defect such as a seal pattern burst can be prevented.

According to the above embodiments of the present invention, the compensation patterns compensating for a phase difference and a height difference between the black matrix and the color filter layer at the same time are formed, thus enhancing the viewing angle.

Also, because the compensation patterns are formed directly on the substrate unlike in the related art where a compensation film is separately manufactured and attached, a thin LCD device may be implemented.

Further, because the compensation patterns are removed from the column spacer region, it is possible to stably maintain a cell gap between two substrates.

Furthermore, because the compensation patterns are removed from the seal pattern region, a seal pattern burst can be prevented.

As described above, the compensation patterns are formed on an inner surface of a substrate, thus enhancing the viewing angle, decreasing contamination due to foreign particles, and providing a slim LCD device.

Also, a burst defect of the seal pattern which may be caused when the compensation patterns are formed on an inner surface of a substrate is improved, thus providing an LCD device that may stably maintain the cell gap between two substrates.

It will be apparent to those skilled in the art that various modifications and variations can be made in the present invention without departing from the spirit or scope of the invention. Thus, it is intended that the present invention cover the modifications and variations of this invention provided they come within the scope of the appended claims and their equivalents.

What is claimed is:

1. A liquid crystal display device comprising:

a first substrate;

a black matrix formed in a matrix configuration on the first substrate;

a compensation layer capable of compensating the optical phase difference disposed above the black matrix and including a plurality of compensation patterns separated by a predetermined region from each other where the compensation layer has been removed;

a color filter layer disposed between patterns of the black matrix; and

a column spacer disposed in a region including at least the predetermined region,

wherein the color filter layer has a stripe configuration, wherein the color filter layer comprises color filters spaced apart by a predetermined interval from one another in a first direction on the black matrix,

wherein the color filter layer covers an overall portion of an upper surface of the black matrix in a second direction,

wherein the column spacer is formed on the predetermined region and a partial region of the compensation patterns, wherein a common electrode is formed on the black matrix and the compensation patterns of the first substrate, and wherein the column spacer is contacted with the common electrode corresponding to the predetermined region of the compensation patterns.

2. The liquid crystal display device according to claim 1, further comprising: a pixel electrode formed on a second substrate, wherein a seal pattern is formed on the common electrode.

3. The liquid crystal display device according to claim 1, wherein the common electrode includes a groove recessed toward the black matrix, and the column spacer is formed on the groove of the common electrode.

4. The liquid crystal display device according to claim 1, wherein the compensation patterns are not formed on the first substrate corresponding to the edge region.

5. The liquid crystal display device according to claim 1, wherein the compensation patterns are formed of a reactive mesogen.

6. A liquid crystal display device comprising:

a first substrate;

a black matrix formed in a matrix configuration on the first substrate;

a compensation layer capable of compensating the optical phase difference disposed above the black matrix and including a plurality of compensation patterns separated by a predetermined region from each other where the compensation layer has been removed;

a column spacer disposed in a region including at least the predetermined region;

a second substrate disposed facing the first substrate;

a liquid crystal layer interposed between the first substrate and the second substrate, and

a color filter layer disposed between patterns of the black matrix,

wherein the second substrate includes a pixel electrode, wherein the color filter layer has a stripe configuration, wherein the color filter layer comprises color filters spaced apart by a predetermined interval from one another in a first direction on the black matrix,

wherein the color filter layer covers an overall portion of an upper surface of the black matrix in a second direction, wherein the column spacer is formed on the predetermined region and a partial region of the compensation patterns, wherein a common electrode is formed on the black matrix and the compensation patterns of the first substrate, and wherein the column spacer is contacted with the common electrode corresponding to the predetermined region of the compensation patterns.

7. The liquid crystal display device according to claim 6, further comprising a seal pattern formed in an edge region of the first and second substrates.

8. The liquid crystal display device according to claim 7, wherein the compensation patterns are not formed on the first substrate corresponding to the edge region.

9. The liquid crystal display device according to claim 7, wherein the seal pattern is directly formed on the first substrate.

10. The liquid crystal display device according to claim 6, wherein the compensation patterns are formed of a reactive mesogen.

* * * * *

专利名称(译)	液晶显示装置及其制造方法		
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[标]申请(专利权)人(译)	KIM KYEONG 金 AHN BYUNG GUN		
申请(专利权)人(译)	KIM KYEONG 金 AHN BYUNG GUN		
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[标]发明人	KIM KYEONG JIN AHN BYUNG GUN		
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摘要(译)

提供了一种可以改善图像质量的液晶显示 (LCD) 装置及其制造方法。
一种液晶显示装置，包括：第一基板;在第一基板上以矩阵结构形成的黑矩阵;补偿层，设置在黑矩阵上方，并包括多个补偿图案，所述补偿图案将已经去除了补偿层的预定区域彼此分开;柱状间隔物设置在至少包括预定区域的区域中。

